L Number	Hits	Search Text	DB	Time stamp
6	39224		USPAT;	2004/09/20 08:59
		and (photoresit or photosensitive) and	US-PGPUB;	
		<pre>(coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)</pre>	EPO; JPO; DERWENT	
7	19889	((substrate\$1 or wafer\$1 or workpiece\$1)	USPAT;	2004/09/20 08:55
l	15005	and (photoresit or photosensitive) and	US-PGPUB;	2001, 03, 20 00103
		(coat\$4 or layer\$4) and (exposur\$4 or	EPO; JPO;	
		radiat\$4 or irradiat\$4)) and ((substrate\$1	DERWENT	
		or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)		
8	9647	(((substrate\$1 or wafer\$1 or workpiece\$1)	USPAT;	2004/09/20 08:56
	504,	and (photoresit or photosensitive) and	US-PGPUB;	2001,03,20 00100
		(coat\$4 or layer\$4) and (exposur\$4 or	EPO; JPO;	
		radiat\$4 or irradiat\$4)) and ((substrate\$1	DERWENT	
		or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4)) and (exposur\$4 or radiat\$4 or		İ
		irradiat\$4)		
9	1764	''''	USPAT;	2004/09/20 08:56
		and (photoresit or photosensitive) and	US-PGPUB; EPO; JPO;	
		(coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1	DERWENT	
		or wafer\$1 or workpiece\$1) same		
		(photoresit or photosensitive) same		
		(coat\$4 or layer\$4)) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((substrate\$1	İ	
		or wafer\$1 or workpiece\$1) same		
}		(photoresit or photosensitive) same		
1		(coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same (ink\$1 or		<u> </u>
	İ	liquid\$1 or fluid\$1)) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)	IICDAM.	2004/09/20 08:58
10	203	<pre>(((((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or</pre>	USPAT; US-PGPUB;	2004/09/20 00:30
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		1
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
	<u> </u>	radiat\$4 or irradiat\$4)		<u> </u>

11	119	(((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:07
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
	1	and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		·
		workpiece\$1) same (photoresit or		•
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
	ĺ	or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
	į	eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)		
13	8	(((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:00
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	l
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
	j .	and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
	İ	photosensitive) same (coat\$4 or layer\$4)		i
!		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
	1	(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
	1	eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
	1	layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit	1	
	1	or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
	1	or eject\$4 or spray\$4)) same (exposur\$4 or		
	1	radiat\$4 or irradiat\$4))) and		
		((substrate\$1 or wafer\$1 or workpiece\$1)		
L	1	same (rotat\$4 or circul\$4))	<u> </u>	<u> </u>

			·	
12	77	((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:02
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		<pre>and (exposur\$4 or radiat\$4 or irradiat\$4))</pre>	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		<pre>photosensitive) same (coat\$4 or layer\$4))</pre>		
		<pre>and (exposur\$4 or radiat\$4 or irradiat\$4))</pre>		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		<pre>photosensitive) same (coat\$4 or layer\$4)</pre>		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
i		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		1
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
1		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4)) same (exposur\$4 or		
		radiat\$4 or irradiat\$4))		

	10	[TIODAM.	1 2004 (00 (20 00.10)
14	42	((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:12
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	!
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		!
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
	ł	same (mask\$4 or pattern\$4) same ((ink\$1 or		
	1	_		
	1	liquid\$1 or fluid\$1) with (jet\$4 or		
	[eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		1
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) not		
		(((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
	1	and ((substrate\$1 or wafer\$1 or		
	· 	workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
-		or radiat\$4 or irradiat\$4)) and		
1		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
1		pattern\$4) same (ink\$1 or liquid\$1 or		
	1	fluid\$1)) and (exposur\$4 or radiat\$4 or		
	1	irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
				1
}		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
1		layer\$4) same ((mask\$4 or pattern\$4) with		
1		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4)) same (exposur\$4 or		
[radiat\$4 or irradiat\$4)))	1	
			-	

15	84	(((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:12
		workpiece\$1) and (photoresit or	US-PGPUB;	
		photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
		and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
	*	and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		j
		eject\$4 or spray\$4))) and (exposur\$4 or		
	1	radiat\$4 or irradiat\$4)) not		
		((((((substrate\$1 or wafer\$1 or		
		workpiece\$1) and (photoresit or		
		photosensitive) and (coat\$4 or layer\$4)		
]
		and (exposur\$4 or radiat\$4 or irradiat\$4))		[
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4))		
		and (exposur\$4 or radiat\$4 or irradiat\$4))		
		and ((substrate\$1 or wafer\$1 or		
		workpiece\$1) same (photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4)) and (exposur\$4		
		or radiat\$4 or irradiat\$4)) and		
		((photoresit or photosensitive) same		Ĭ
		(coat\$4 or layer\$4) same (mask\$4 or		
		pattern\$4) same (ink\$1 or liquid\$1 or		
		fluid\$1)) and (exposur\$4 or radiat\$4 or		
		irradiat\$4)) and ((photoresit or		
		photosensitive) same (coat\$4 or layer\$4)		
		same (mask\$4 or pattern\$4) same ((ink\$1 or		
		liquid\$1 or fluid\$1) with (jet\$4 or		
		eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4)) and ((photoresit		
		or photosensitive) same (coat\$4 or		
		layer\$4) same ((mask\$4 or pattern\$4) with		
		(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
		or eject\$4 or spray\$4))) and (exposur\$4 or		
		radiat\$4 or irradiat\$4))		

16	19 ((((((substrate\$1 or wafer\$1 or	USPAT;	2004/09/20 09:15
	workpiece\$1) and (photoresit or	US-PGPUB;	
	photosensitive) and (coat\$4 or layer\$4)	EPO; JPO;	
·	and (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
	<pre>photosensitive) same (coat\$4 or layer\$4))</pre>		
j	and (exposur\$4 or radiat\$4 or irradiat\$4))		
]	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4)) and (exposur\$4		
	or radiat\$4 or irradiat\$4)) and		
	((photoresit or photosensitive) same		
	(coat\$4 or layer\$4) same (mask\$4 or		
	pattern\$4) same (ink\$1 or liquid\$1 or		
	fluid\$1)) and (exposur\$4 or radiat\$4 or		
	irradiat\$4)) and ((photoresit or		1
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4) same ((ink\$1 or		
	liquid\$1 or fluid\$1) with (jet\$4 or		
	eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)) not		
	((((((substrate\$1 or wafer\$1 or	İ	
	workpiece\$1) and (photoresit or		
	photosensitive) and (coat\$4 or layer\$4)		
	and (exposur\$4 or radiat\$4 or irradiat\$4))		
	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
	photosensitive) same (coat\$4 or layer\$4))		
1	and (exposur\$4 or radiat\$4 or irradiat\$4))		
1	and ((substrate\$1 or wafer\$1 or		
	workpiece\$1) same (photoresit or		
1	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4)) and (exposur\$4		
	or radiat\$4 or irradiat\$4)) and		
	((photoresit or photosensitive) same		
	(coat\$4 or layer\$4) same (mask\$4 or		
	pattern\$4) same (ink\$1 or liquid\$1 or		
	fluid\$1)) and (exposur\$4 or radiat\$4 or		
	irradiat\$4)) and ((photoresit or		
	photosensitive) same (coat\$4 or layer\$4)		
	same (mask\$4 or pattern\$4) same ((ink\$1 or		
	liquid\$1 or fluid\$1) with (jet\$4 or		
	eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4)) and ((photoresit		
	or photosensitive) same (coat\$4 or		
	layer\$4) same ((mask\$4 or pattern\$4) with		
	(ink\$1 or liquid\$1 or fluid\$1) with (jet\$4		
	or eject\$4 or spray\$4))) and (exposur\$4 or		
	radiat\$4 or irradiat\$4))) and (rotat\$4 or		
	circul\$4)		

95 [(((((((ubstrates)) or wafers) or workpieces)] and (notores) or photosensitive) and (coats4 or layers4) and (substrates) or wafers) or photosensitive) same (coats4 or layers4) and (substrates) or wafers) or photosensitive) same (coats4 or layers4) and (substrates) or wafers) or photosensitive) same (coats4 or layers4) and (substrates) or wafers) or photosensitive) same (coats4 or layers4) and (coats4 or layers4) and ((photoresit or photosensitive) same (coats4 or layers4) or radiats4 or irradiats40) and ((photoresit or photosensitive) same (coats4 or layers4) and ((photoresit or photosensitive) same (coats4 or layers4) same (mansk4 or patterns4) and the photosensitive) same (coats4 or layers4) same (mansk4 or patterns4) same (mansk4 or patterns4) and (coats4 or layers4) same (mansk4 or patterns4) same (coats4 or layers4) same (mansk4 or patterns4) same (coats4 or layers4) and (exposurs4 or radiats4) or radiats40) and (exposurs4 or radiats40) and (exposurs4 or radiats40) and (exposurs4 or radiats40) and (exposurs4 or radiats40) and (exposurs4 or radiats40) and (exposurs4 or radiats40) and ((photoresit or photosensitive) same (coats4 or layers4)) and ((substrates1) or wafers1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4) and ((photoresit or photosensitive) same (coats4 or layers4) and (coats4 or layers4) same (mansk4) or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk4 or patterns4) same (mansk					
iphotosensitive) and (coat84 or layer84) and (substrate\$1 or wafer\$2 or adiat\$4 or iradiat\$4	17	1 ' '		USPAT;	2004/09/20 09:16
and (exposurs% or radiats% or irradiats%)) and (substrates) or wafer% or photosensitive) same (photoresit or photosensitive) same (coats% or layers%)) and (exposurs% or radiats% or irradiats%)) and (exposurs% or radiats% or irradiats%)) and (exposurs% or radiats% or irradiats%)) and (exposurs% or radiats% or layers%) same (mask% or patterns%)) and (exposurs% or radiats% or irradiats%)) and (iphotoresit or photoresit or photosensitive) same (coats% or layers%) same (mask% or patterns%) and (inhalor or fluids%)) and (exposurs% or radiats% or irradiats%)) and (photoresit or photosensitive) same (coats% or layers%) same (mask% or patterns%) same (links% or ilquids%) or fluids%) with (jets% or ejects% or sprays%))) and (exposurs% or workpieces%) and (photoresit or photosensitive) and (coats% or layers%) and (exposurs% or radiats% or irradiats%)) and (substrates%) or wafers%) or workpieces%) same (photoresit or photosensitive) same (photoresit or photosensitive) and (coats% or layers%) and (substrates%) or radiats% or irradiats%)) and (substrates%) or wafers% or or photosensitive) same (coats% or layers%) same (mask% or patterns%) and (exposurs% or radiats% or irradiats%) or irradiats%) and (substrates%) or makers% or patterns%) same (mask% or patterns%) and (exposurs% or photosensitive) same (coats% or layers%) same (mask% or patterns%) and (exposurs% or irradiats%)) and (photoresit or photosensitive) same (coats% or layers%) same (mask% or patterns%) and (exposurs% or radiats% or irradiats%) and (photoresit or photosensitive) same (coats% or layers%) same (mask% or patterns%) and (sposurs% or radiats% or irradiats%)) and (exposurs% or rejects% or sprays%))) and (exposurs% or rejects% or sprays%)) and (exposurs% or rejects% or sprays%)) and (exposurs% or rejects% or sprays%)) and (substrates%) or hereins%) or rediats% or irradiats%) and (substrate			-	-	
and ((substrate\$) or wafer\$) or workpiece\$) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (substrate\$1 or wafer\$1 or photosensitive) same (coat\$4 or layer\$4) and ((substrate\$1 or wafer\$1 or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4)) and (exposur\$4 or radiat\$4 or larediat\$4) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (anak\$4 or layer\$4) same (mask\$4 or pattern\$4) same (radiat\$5 or radiat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (inn\$1 or liquid\$1 or radiat\$1) in (exposur\$4 or radiat\$4 or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (fink\$1 or liquid\$1 or finid\$1) with (jet\$4 or radiat\$4 or irradiat\$4)) not ((((((substrate\$1) or wafer\$1 or workpiece\$1) and (photoresit or yorkpiece\$1) and (photoresit or photosensitive) same (coat\$4 or layer\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or radiat\$4 or irradiat\$4) irradiat\$4) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1) or liquid\$1 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) same (ink\$1 or liquid\$1 or fivid\$1) with (jet\$4 or pattern\$4) same (ink\$1) or liquid\$1 or radiat\$4 or irradiat\$4) irradiat\$4 or radiat\$4 or irradiat\$4) irradiat\$4 or radiat\$4 or irradiat\$4) or irradiat\$4 or radiat\$4 or irradiat\$4) or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$					
workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (exposur\$4 or radiat\$4 or layer\$4)) and (exposur\$5 or wafor\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) or radiat\$4 or irradiat\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and (exposur\$4 or pattern\$4) same (mask\$4 or pattern\$4) same (mask\$4 or pattern\$4) same (mask\$4 or pattern\$4) same (mask\$4 or layer\$4) same (coat\$4 or layer\$4) same (mask\$4 or photosensitive) same (coat\$4 or layer\$4) same (same (mask\$4 or layer\$4) same exposur\$4 or radiat\$4)) not ((((((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or photosensitive) and (coat\$4 or layer\$4) and ((substrate\$1 or wafer\$1 or same (mask\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or photosensitive) same (coat\$4 or layer\$4)) and (substrate\$1 or vafer\$1 or or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) or radiat\$4 or radiat\$4 or irradiat\$4) or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or radiat\$4 or partern\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (exposur\$4 or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) with (ink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or eject\$4 or spra\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) ind (exposur\$4 or photosensitive) same (coat\$4 or layer\$4) and ((substrate\$1 or wafer\$1 or workpiece\$1) and (photoresit or photosensitive) same (coat\$4 or layer\$4) and (exposur\$4) and (exposur\$4 or radia		an	d (exposur\$4 or radiat\$4 or irradiat\$4))	DERWENT	
photosensitive) same (coats4 or largers41) and (exposurs4 or radiats4 or irradiats4)) and (substrate\$1 or wafer\$1 or workpiece\$1) same (photoseit or photosensitive) same (coats4 or photosensitive) same (coats4 or coats4 or pattern\$4]) and (exposurs4 coats4 or layer\$4] same (mask\$4 or pattern\$4] same (ink\$1 or liquid\$1 or fluid\$1]) and (exposur\$4 or radiat\$4 or irradiat\$4]) and ((photoresit or photosensitive) same (coats4 or layer\$4) same (mask\$4 or pattern\$4] same (radiat\$4 or irradiat\$4]) and ((photoresit or photosensitive) same (coats4 or layer\$4) same (mask\$4 or pattern\$4]) and (exposur\$4 or eject\$4 or spray\$4]))) and (exposur\$4 or coats6 or layer\$4])) and (exposur\$4 or coats6 or spray\$4])) and (exposur\$4 or radiat\$4]) and (exposur\$4 or radiat\$4 or layer\$4]) same (mas\$4 or pattern\$4]) and (exposur\$4 or radiat\$4 or irradiat\$4]) and (exposur\$4 or pattern\$4] same (mask\$4 or pattern\$4] same (mask\$4 or photosensitive) same (coat\$4 or layer\$4] photosensitive) same (coat\$4 or layer\$4] photosensitive) same (coat\$4 or layer\$4] or photosensitive) same (coat\$4 or radiat\$4 or irradiat\$4]) and (exposur\$4 or radiat\$4]) and (exposur\$4 or radiat\$4 or irradiat\$4]) and (exposur\$4 or reject\$4 or spray\$4])) and (exposur\$4 or reject\$4 or spray\$4])) and (exposur\$4 or rediat\$4 or irradiat\$4]) and (exposur\$4 or rediat\$4 or irradiat\$4]) and (exposur\$4 or rediat\$4 or irradiat\$4]) and (exposur\$4 or photosensitive) same (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4) and (exposur\$4 or photosensitive) same (coat\$4 or laye		an	d ((substrate\$1 or wafer\$1 or		
and (exposurs4 or radiats4) and (substrates) or waters1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4) same (mask4 or patterns4)) and (exposurs4 or radiats4 or irradiats4)) and ((photoresit or photosensitive) same (mask4 or patterns4) same (coats4 or lines4) patterns4) same (ink1 or lines4) patterns4) same (ink1 or lines4) same (mask4 or patterns4) same (ink8) or liquids1) and (exposurs4 or radiats4 or irradiats4)) and (photoresit or photosensitive) same (coats4 or layers4) same (mask54 or patterns4) same (ink8) or liquids1 or fluids1) with (jets4 or ejects4 or spray41)) and (exposurs4 or radiats4 or irradiats4)) not ((((((substrates1) or waters1 or workpieces1) and (shotoresit or photosensitive) same (coats4 or layers4)) and ((substrates1) or waters1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4)) and (substrates1 or waters1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4) and (substrates1 or waters1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4) same (mask34 or patterns4)) and (exposurs4 or radiats4 or irradiats4)) and (photoresit or photosensitive) same (photoresit or photosensitive) same (coats4 or layers4) same (mask34 or patterns4) same (ink1 or liquids1 or pluids1) and ((photoresit or photosensitive) same (coats4 or layers4) same (mask34 or patterns4) same (ink1 or liquids1 or liquids1 or fluids1) with (jets4 or ejects4 or spray54))) and (exposurs4 or radiats4 or irradiats4) and (photoresit or photosensitive) same (coats4 or layers4) same (mask4 or patterns4) same (ink1 or liquids1 or liquids1 or fluids1) with (jets4 or ejects4 or spray54))) and (exposurs4 or radiats4 or irradiats4)) and (photoresit or photosensitive) same (coats4 or layers4) and (substrates1 or wafers1 or workpieces1) same (photoresit or photosensitive) same (coats4 or layers4) and (exposurs4 or radiats4)) and (exposurs4 or radiats4 or irradiats4)) and (photoresit or photosensit or photosensitive) same (coats4 or layers4		wo	rkpiece\$1) same (photoresit or		
and ((substrate\$) or wafer\$) or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or partern\$4) and (exposur\$4 or radiat\$4 or irradiat\$4) and (photoresit or photosensitive) same (photoresit or photosensitive) same pattern\$4) same (ink\$1 or liquid\$1 or fluid\$1) and (exposur\$4 or radiat\$4 or irradiat\$4) and ((photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) same (fink\$1 or liquid\$1 or fluid\$1) with (jet\$4 or eject\$4 or spray\$4))) and (exposur\$4 or radiat\$4 or irradiat\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4) and (substrate\$1 or ((((((substrate\$1 or wafer\$1 or photosensitive) same (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4 or irradiat\$4()) and (exposur\$4 or radiat\$4()) and (exposur\$4		ph	otosensitive) same (coat\$4 or layer\$4))		
workpieces] same (photoresit or photosensitive) same (coats4 or layers4) same (mask84 or patterns4)) and (exposurs4 or radiats4) or irradiats54); and ((photoresit or photosensitive) same (coats4 or layers4) same (mask84 or patterns4) same (sak84 or patterns4) same (ink81 or liquids1 or fluids1) same (fink81 or liquids1 or fluids1) same (fink81 or liquids1 or photosensitive) same (coats4 or layers4) same (mask84 or patterns4) same (fink81 or liquids1 or fluids1) with (jets4 or ejects4 or spray4))) and (exposurs4 or radiats4 or irradiats4) not ((((((substrate51) or wafer\$)) or workpiece\$1) and (shotoresit or layers4) and (exposurs4 or radiats4 or layers4) and (exposurs54 or radiats54 or layers4) and (exposurs64 or radiats6 or layers64) and (exposurs64 or radiats6 or layers64) and (exposurs64 or radiats6 or layers64) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coats6 or layers64) same (mask84 or patterns44) and (exposurs64 or radiats6 or layers64) same (mask84 or layers64) same (mask84 or layers64) same (coats6 or layers64) same		an	d (exposur\$4 or radiat\$4 or irradiat\$4))		
photosensitive) same (coats4 or layers4) same (mask34 or pattern54)) and (exposurs4 or radiats4 or irradiats4)) and (exposurs4 or radiats4 or irradiats4)) and ((photoresit or photosensitive) same (coats4 or layers4) same (mask54 or pattern54) same (ink51 or liquid51 or fluid51)) and (exposurs4 or radiats4 or irradiats4)) and ((photoresit or layers4) services or sprays4)) and (exposurs4 or ejects4 or sprays4))) and (exposurs4 or radiats4 or irradiats54)) not (((((((substrate51 or wafer51 or workpiece51) and (hotoresit or photosensitive) and (coat54 or irradiats4))) and (substrate51 or wafer51 or workpiece51) and (coat54 or irradiats4))) and (substrate52 or wafer51 or workpiece51) same (photoresit or photosensitive) same (coat54 or layer54)) and (substrate52 or wafer51 or workpiece51) same (photoresit or photosensitive) same (coat54 or layer54)) and (substrate52 or wafer51 or workpiece51) same (photoresit or photosensitive) same (coat54 or layer54) and (substrate53 or wafer50 or photosensitive) same (coat54 or layer54) same (mask54 or pattern54)) and (exposur54 or radiat54 or irradiat54)) and (exposur54 or radiat54 or irradiat54)) and (exposur54 or photosensitive) same (coat54 or layer54) same (mask54 or pattern54)) and ((photoresit or photosensitive) same (coat54 or layer54) same (mask54 or pattern54) same (ink51 or liquid51 or fluid51) and (exposur54 or radiat54 or irradiat54) and ((photoresit or photosensitive) same (coat54 or layer54) same (mask54 or pattern54) same (ink51 or liquid51 or fluid51) with (jet64 or radiat54 or irradiat54)) and (iphotoresit or photosensitive) same (coat54 or layer54) same (mask54 or pattern54) with (ink51 or liquid51 or fluid51) with (jet64 or radiat54 or irradiat54)) and (iphotoresit or photosensitive) same (coat54 or layer54) and (substrate51 or wafer51 or vorkpiece51) same (photoresit or photosensitive) same (coat54 or layer54) same (mask64 or pattern54) and (exposur54 or radiat54 or irradiat54)) and ((photoresit or maker51 or photosensitive) same (coat54 or layer54) same (mask		an	d ((substrate\$1 or wafer\$1 or		
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or radiats4 or irradiats4)) and ((photoresit or photosensitive) same (coats4 or layer\$4) same (mask\$4 or pattern\$4) same (ink\$1 or fluid\$1) or fluid\$1]) and (exposur\$4 or radiat\$4 or irradiat\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4)) and (exposur\$4 or layer\$4) same (mask\$4 or pattern\$4) same ((ink\$1 or layer\$4) same (mask\$4 or pattern\$4) same ((ink\$1 or layer\$4)) and (exposur\$4 or radiat\$4 or irradiat\$4) and (substrate\$1 or wafer\$1 or workpiece\$1) ame (photosensit or photosensitive) same (coat\$4 or layer\$4)) and (substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and (substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or properties\$1) and (substrate\$1 or irradiat\$4) and (coat\$4 or layer\$4) and (coat\$4 or layer\$4) and (coat\$4 or layer\$4) and (coat\$4 or layer\$4) same (mask\$4 or pattern\$4) and (exposur\$4 or radiat\$4 or irradiat\$4 or i					
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patterns4) same (inks1 or liquids1 or fluids1) and (exposurs4 or radiats4 or irradiats4)) and ((photoresit or photosensitive) same (coats4 or layers4) same (mask4 or patterns4) same ((inks1 or liquids1 or fluids1) with (jets4 or ejects4 or sprays4))) and (exposurs4 or radiats4 or irradiats4)) not (((((((((((substrateS1 or wafer\$1 or workpiece\$1) and (photoresit or photosensitive) and (coat\$4 or layer\$4) and (exposur\$4 or radiat\$4 or irradiat\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) amms (photoresit or photosensitive) same (coat\$4 or layer\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4)) and ((substrate\$1 or wafer\$1 or workpiece\$1) same (photoresit or photosensitive) same (coat\$4 or layer\$4) same (mask8 or patterns4) same (mask8 or patterns4) same (mask8 or patterns4) same (mask8 or patterns4) same (mask8 or patterns4) same (ink\$1 or liquid\$1 or fluid\$1) and ((substrate\$1 or layer\$4) same (mask8 or patterns4) same (ink\$1 or liquid\$1 or fluid\$1) and ((substrate\$1 or alyer\$4) same (ink\$1 or liquid\$1 or fluid\$1) and (substrate\$1 or alyer\$4) same (ink\$1 or liquid\$1 or fluid\$1) and ((substrate\$1 or alyer\$4) same (ink\$1 or liquid\$2 or lipuid\$3 or liquid\$3 or liquid\$3 or liquid\$3 or liquid\$3 or liquid\$3 or liq			•		
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